

**REMARKS**

The Examiner is thanked for the thorough examination of the present application. The Office, however, tentatively rejected all claims 1-19 as allegedly anticipated by U.S. Published Application 2002/0177073 (to Melisaris). In this response, claims 1, 6, 7, 9, 11, 14, and 17 have been amended, and claims 3-5 have been canceled.

**Response to Rejections Under 35 U.S.C. 102 (e)**

The Office Action rejected claims 1 -19 under 35 U.S.C. 102 (e) as allegedly anticipated by Melisaris (US 2002/0177073 A1).

In order to more clearly identify a novel and non-obvious feature of this application, Applicants have amended claim 1 to define the negative photoresist composition only comprising **unsaturated resin** selected from the group consisting of homopolymers, copolymers, and combinations thereof, which the homopolymers and the copolymers are synthesized by at least one monomer selected from the group consisting of styrene, methyl styrene, acrylic acid, acrylate, methyl acrylic acid, methyl acrylate, vinyl ether, and combinations thereof. In addition, the **unsaturated resin** must have a molecular weight in the range from 5,000 to 250,000 and an acid value between 50 and 250mgKOH/g. Support of the amendment can be found at least on page 5, lines 5-17. No new matter is added. Furthermore, claims 6, 7, 9, 11, 14, and 17 are amended consistent with an amendment to claim 1.

Applicants respectfully submit that amended claim 1 is neither anticipated by, nor obvious in view of Melisaris, and the rejection of claim 1 should be withdrawn.

To further elaborate, claim 1 recites the negative photoresist composition comprising unsaturated resin, synthesized by at least one monomer selected from the group consisting of

styrene, methyl styrene, acrylic acid, acrylate, methyl lacrylic acid, methyl acrylate, vinyl ether, or combinations thereof. Namely, the unsaturated resin only has reactive C=C subchain, rather than an epoxy group. In contrast, Melisaris discloses a composition comprising a radiation-curable and cationically polymerizable organic component. Pleasing referring to Para. [102] of Melisaris, the radiation-curable and cationically polymerizable organic component, however, is epoxycresol novolac or epoxycresol novolac having at least two epoxy groups. Melisaris does not teach or suggest that the resin is synthesized by at least one monomer selected from the group consisting of styrene, methyl styrene, acrylic acid, acrylate, methyl lacrylic acid, methyl acrylate, vinyl ether, or combinations thereof. In addition, Melisaris does not disclose the resin has a molecular weight in the range from 5,000 to 250,000 and an acid value between 50 and 250mgKOH/g. The effect of unsaturated resin with reactive C=C subchain and acid value in particular molecular weight range is not expectable in Melisaris et al.

In addition, when the photoresist composition is coated to form a photoresist film and developed with an alkaline developing solution, a photoresist pattern having excellent cross-sectional profile, high fidelity and alkali resistance can be formed due to the specific acid value. This character is not taught or suggested by Melisaris et al.

As the cited reference does not teach or suggest the features defined in claim 1, claim 1 is allowable over the cited reference. Insofar as claims 2 and 6-19 depend from claim 1, these claims are also allowable at least by virtue of their dependency.

Should the Examiner believe that a teleconference would be helpful to expedite the examination of this application, the Examiner is invited to contact the undersigned.

No fee is believed to be due in connection with this amendment and response. If, however, any fee is deemed to be payable, you are hereby authorized to charge any such fee to Deposit Account No. 20-0778.

Respectfully submitted,

By:

  
Daniel R. McClure, Reg. No. 38,962

Thomas, Kayden, Horstemeyer & Risley, LLP  
100 Galleria Pkwy, NW  
Suite 1750  
Atlanta, GA 30339  
770-933-9500